

Amendment to the Claims:

This listing of claims replaces all prior versions, and listings, of claims in the application:

1. (currently amended) A method comprising:
applying carbon dioxide to a surface of a reticle; and
forming a solid carbon dioxide layer on the surface of the reticle at a temperature below a sublimation temperature of carbon dioxide, the solid carbon dioxide layer preventing particles from contacting the surface of the reticle; and
spraying the surface of the reticle with carbon dioxide inside a lithography tool.

2. (original) The method of Claim 1, wherein said applying comprises spraying the surface of the reticle with carbon dioxide and removing particles from the surface with carbon dioxide snow.

3. (original) The method of Claim 1, wherein said applying comprises spraying carbon dioxide snow at a grazing angle with respect to the surface of the reticle.

4. (original) The method of Claim 1, further comprising cooling the reticle to a temperature below a sublimation

temperature of carbon dioxide before said forming a solid carbon dioxide layer on the surface of the reticle.

5. (original) The method of Claim 1, wherein said forming a solid carbon dioxide layer on the surface of the reticle comprises spraying carbon dioxide snow at a substantially 90 degree angle with respect to the surface of the reticle.

6. (original) The method of Claim 1, further comprising:
enclosing the reticle with the solid carbon dioxide layer in a carrier; and

maintaining a temperature around the reticle below a sublimation temperature of carbon dioxide.

7. (currently amended) The method of Claim 6, further comprising removing the carrier and inserting the reticle with the solid carbon dioxide layer in a lithography tool.

8. (original) The method of Claim 1, further comprising raising a temperature around the reticle above a carbon dioxide sublimation temperature.

9. (original) The method of Claim 1, further comprising removing the solid carbon dioxide layer from the surface of the reticle.

10. (original) The method of Claim 1, further comprising spraying the surface of the reticle with carbon dioxide inside a lithography tool.

11. (original) The method of Claim 1, further comprising reflecting radiation off the surface of the reticle in a lithography tool.

12. (original) The method of Claim 1, further comprising reflecting extreme ultraviolet radiation off the surface of the reticle in a lithography tool.

13-17. (canceled)

18. (new) A method comprising:

spraying carbon dioxide to remove particles on a surface of a reticle;

cooling the reticle to a temperature below a sublimation temperature of carbon dioxide;

forming a solid carbon dioxide layer on the surface of the cooled reticle to prevent particles from contacting the surface of the reticle;

warming the reticle to sublimate the solid carbon dioxide layer; and

spraying gas to remove particles on the surface.

19. (new) A method for cleaning a surface of a reticle inside a lithography tool wherein the improvement comprises spraying the surface of the reticle with carbon dioxide.

20. (new) A method comprising:

placing a pellicle over a reticle;

applying carbon dioxide to a surface of the pellicle;

forming a solid carbon dioxide layer on the surface of the pellicle at a temperature below a sublimation temperature of carbon dioxide to prevent particles from contacting the surface of the pellicle; and

removing the pellicle from the reticle.